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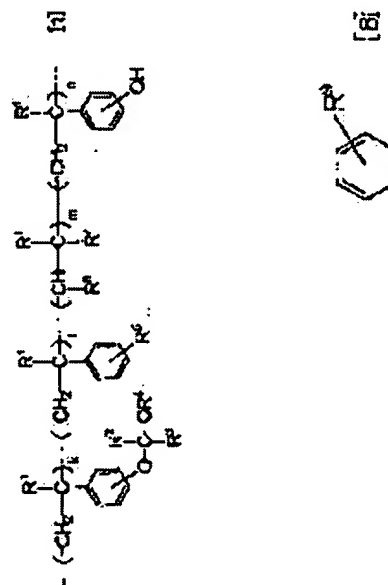
JP

(54) RESIST COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a resist composition containing a chemically amplified resist composition and giving a rectangular ultrafine pattern.

SOLUTION: The invention discloses a polymer expressed by general formula [1] and a resist composition containing the polymer [R1 is H or methyl; R2 and R3 are each H or a 1-6C alkyl; R4 is a 1-6C alkyl, an aralkyl or phenyl; R5 is H, a 1-6C alkyl, a 1-6C alkoxy, t-butoxycarbonyloxy, tetrahydropyranyloxy, acetyloxy or OCH₂COOC(CH₃)₃; R6 is H or cyano; R7 is COOR8 (R8 is a 1-6C alkyl or a 7-12C bridged alicyclic hydrocarbon group), cyano or a group of general formula [8] (R9 is H, a 1-6C alkyl or a 1-6C alkoxy)].



LEGAL STATUS

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